Available online at www.sciencedirect.com
SCIENCE DIRECT®
ELSEVIER
Journal of Photochemistry and Photobiology A: Chemistry 166 (2004) 163
Journal of Photochemistry and Photobiology A:Chemistry
www.elsevier.com/locate/jphotochem

Author Index of Volume 166

Abe, R. 115
Abe, Y. 81
Altobello, S. 91, 99
Arakawa, H. 69, 81, 115

Bandyopadhyay, T. 33
Bignozzi, C.A. 91, 99

Canulescu, S. 135
Caramori, S. 91, 99

David, C. 135
Ding, X. 129
Domcke, W. 19

Egorova, D. 19

Fujihira, M. 45
Fukuzumi, S. 57
Furube, A. 69

Gobrecht, J. 135

Hara, K. 69
Hayashi, K. 141
Hilczer, M. 33
Hiramatsu, H. 141
Hirano, M. 141
Honda, K. 63
Hosomizu, K. 57
Hosono, H. 141

Imahori, H. 57

Jeon, S. 149

Kamioka, H. 141
Katoh, R. 69
Kawaguchi, Y. 129
Kimura, M. 57
Kitamura, T. 75
Kopitkovas, G. 135
Kose, M. 9
Kubo, Y. 123
Kumagai, T. 123
Kurosaki, R. 129

Lakhmiri, R. 91
Larramona, G. 91
Lippert, T. 135

Manabe, T. 123
Maria, J. 149
Marzanni, G. 91
Mizuta, S. 123
Murai, M. 69
Murata, S. 69

Nagao, Y. 81
Nakamura, K. 75
Nakamura, R. 107
Nakanaga, T. 3
Nakato, Y. 107
Narazaki, A. 129
Niino, H. 129

Odobel, F. 99
Ohmura, H. 3

Quici, S. 91

Rogers, J.A. 149

Sakomura, M. 45
Sano, S. 81
Sato, T. 81, 129
Sayama, K. 115
Senadeera, G.K.R. 75
Shimakawa, Y. 123
Sugihara, H. 81
Suzuki, H. 155

Tachiya, M. 1, 3, 33, 69
Takabayashi, S. 107
Tamaki, Y. 69
Tsuchiya, T. 123

Wada, Y. 75
Wokaun, A. 135

Yamaguchi, I. 123
Yamaguchi, T. 81
Yanagida, M. 81
Yanagida, S. 75
Yokoyama, Y. 9
Yoshihara, T. 69
Yoshitake, T. 123

Zabri, H. 99

Elsevier B.V.
doi:10.1016/S1010-6030(04)00336-3

Available online at www.sciencedirect.com
SCIENCE DIRECT®
ELSEVIER
Journal of Photochemistry and Photobiology A: Chemistry 166 (2004) 165–167
Journal of Photochemistry and Photobiology A:Chemistry
www.elsevier.com/locate/jphotochem

Subject Index of Volume 166

Ablation
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Allyl iodide
Coherent control of interference between one- and two-photon dissociation of allyl iodide, 3
ArF excimer laser
Low-temperature growth of $La_{0.8}Sr_{0.2}MnO_3$ thin films on $LaAlO_3$ and $SrTiO_3$ substrates by an excimer laser metal organic deposition (ELMOD) process, 123
A–S–D triads
Scanning Maxwell stress microscopy of photo-induced charge separation in A–S–D triad monolayers, 45

Bisbenzothienylethene
Reversible control of properties of materials by thermally irreversible photochromism, 9
Bolometer
Low-temperature growth of $La_{0.8}Sr_{0.2}MnO_3$ thin films on $LaAlO_3$ and $SrTiO_3$ substrates by an excimer laser metal organic deposition (ELMOD) process, 123
Boronic acid function
Sensitization of TiO_2 with ruthenium complexes containing boronic acid functions, 91

C12A7
Photonic materials utilizing naturally occurring nanostructures, 141
Carrier confinement
Photonic materials utilizing naturally occurring nanostructures, 141
Cholesteric liquid crystals
Reversible control of properties of materials by thermally irreversible photochromism, 9
Conducting polymer dyes
Polythiophene-sensitized TiO_2 solar cells, 75
Control of interference
Coherent control of interference between one- and two-photon dissociation of allyl iodide, 3

Density functional theory
Highly efficient photosensitization of TiO_2 with diimine(diketonato)ruthenium(II) complexes, 81
Diastereoselectivity
Reversible control of properties of materials by thermally irreversible photochromism, 9
β-Diketonate
Highly efficient photosensitization of TiO_2 with diimine(diketonato)ruthenium(II) complexes, 81
Dye sensitization
Dawn of the evolution of photoelectrochemistry, 63
Dye-sensitized photocatalysts
Dye-sensitized photocatalysts for efficient hydrogen production from aqueous I^- solution under visible light irradiation, 115
Dye-sensitized solar cell
Microscopic imaging of the efficiency of electron injection from excited sensitizer dye into nanocrystalline ZnO film, 69
Dye-sensitized solar cells
Polythiophene-sensitized TiO_2 solar cells, 75

Elastomer
Nanopatterning with conformable phase masks, 149
Electric field effect
Electric field effect on electron transfer between donor and acceptor in polymer matrix, 33
Electron injection
Microscopic imaging of the efficiency of electron injection from excited sensitizer dye into nanocrystalline ZnO film, 69
Electron transfer
Quantum dynamical simulations of ultrafast photoinduced electron-transfer processes, 19
Porphyrin and fullerene-based photovoltaic devices, 57
Electronic conductor
Photonic materials utilizing naturally occurring nanostructures, 141
Epitaxy
Low-temperature growth of $La_{0.8}Sr_{0.2}MnO_3$ thin films on $LaAlO_3$ and $SrTiO_3$ substrates by an excimer laser metal organic deposition (ELMOD) process, 123
Excitation migration
Electric field effect on electron transfer between donor and acceptor in polymer matrix, 33
Exciton
Photonic materials utilizing naturally occurring nanostructures, 141

F^+ Center
Photonic materials utilizing naturally occurring nanostructures, 141
Fluorescence quenching
Electric field effect on electron transfer between donor and acceptor in polymer matrix, 33
Fulgide
Reversible control of properties of materials by thermally irreversible photochromism, 9
Fullerene
Porphyrin and fullerene-based photovoltaic devices, 57

Homogenizer
Fabrication of beam homogenizers in quartz by laser micromachining, 135
Hydrogen
A nano-modified Si/TiO_2 composite electrode for efficient solar water splitting, 107
Hydrogen production
Dye-sensitized photocatalysts for efficient hydrogen production from aqueous I^- solution under visible light irradiation, 115

INDO/S
Highly efficient photosensitization of TiO_2 with diimine(diketonato)ruthenium(II) complexes, 81

LaCuOS
Photonic materials utilizing naturally occurring nanostructures, 141

Elsevier B.V.
doi:10.1016/S1010-6030(04)00337-5

LaCuOSe
Photonic materials utilizing naturally occurring nanostructures, 141
Langmuir–Blodgett films
Scanning Maxwell stress microscopy of photo-induced charge separation in A–S–D triad monolayers, 45
Laser ablation
Fabrication of beam homogenizers in quartz by laser micromachining, 135
Low-temperature growth
Low-temperature growth of $La_{0.8}Sr_{0.2}MnO_3$ thin films on $LaAlO_3$ and $SrTiO_3$ substrates by an excimer laser metal organic deposition (ELMOD) process, 123
LSMO
Low-temperature growth of $La_{0.8}Sr_{0.2}MnO_3$ thin films on $LaAlO_3$ and $SrTiO_3$ substrates by an excimer laser metal organic deposition (ELMOD) process, 123

Micro-bubble
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Microlens
Fabrication of beam homogenizers in quartz by laser micromachining, 135
Microscope
Microscopic imaging of the efficiency of electron injection from excited sensitizer dye into nanocrystalline ZnO film, 69
MOD
Low-temperature growth of $La_{0.8}Sr_{0.2}MnO_3$ thin films on $LaAlO_3$ and $SrTiO_3$ substrates by an excimer laser metal organic deposition (ELMOD) process, 123

Nanocrystalline TiO_2
Polythiophene-sensitized TiO_2 solar cells, 75
Nanofabrication
Nanopatterning with conformable phase masks, 149
Nano-particles
A nano-modified Si/TiO_2 composite electrode for efficient solar water splitting, 107
Nanosecond-pulsed UV laser
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Nanostructure
Photonic materials utilizing naturally occurring nanostructures, 141
Near field optics
Nanopatterning with conformable phase masks, 149

Optical communication
Organic light-emitting materials and devices for optical communication technology, 155
Organic ionic dyes
Organic light-emitting materials and devices for optical communication technology, 155
Organic IR light-emitting materials
Organic light-emitting materials and devices for optical communication technology, 155
Organic rare-earth complex
Organic light-emitting materials and devices for optical communication technology, 155
Osmium sensitizers
Efficient osmium sensitizers containing 2,2′-bipyridine-4,4′-bisphosphonic acid ligand, 99

Phase mask
Nanopatterning with conformable phase masks, 149
Phosphonic acid functions
Efficient osmium sensitizers containing 2,2′-bipyridine-4,4′-bisphosphonic acid ligand, 99
Photocatalysis
A nano-modified Si/TiO_2 composite electrode for efficient solar water splitting, 107
Photochromism
Reversible control of properties of materials by thermally irreversible photochromism, 9
Photoelectrochemistry
Dawn of the evolution of photoelectrochemistry, 63
A nano-modified Si/TiO_2 composite electrode for efficient solar water splitting, 107
Photoelectrode
Dawn of the evolution of photoelectrochemistry, 63
Photo-induced charge separation
Scanning Maxwell stress microscopy of photo-induced charge separation in A–S–D triad monolayers, 45
Photoinduced electron transfer
Electric field effect on electron transfer between donor and acceptor in polymer matrix, 33
Photolithography
Nanopatterning with conformable phase masks, 149
Photon dissociation
Coherent control of interference between one- and two-photon dissociation of allyl iodide, 3
Photosensitizers
Highly efficient photosensitization of TiO_2 with diimine(diketonato)ruthenium(II) complexes, 81
Photovoltaic devices
Porphyrin and fullerene-based photovoltaic devices, 57
Polymer microparticles
Organic light-emitting materials and devices for optical communication technology, 155
Polymer optical waveguides
Organic light-emitting materials and devices for optical communication technology, 155
Porphyrin
Porphyrin and fullerene-based photovoltaic devices, 57

Quartz
Fabrication of beam homogenizers in quartz by laser micromachining, 135

Redfield theory
Quantum dynamical simulations of ultrafast photoinduced electron-transfer processes, 19
Ruthenium complexes
Sensitization of TiO_2 with ruthenium complexes containing boronic acid functions, 91
Ruthenium(II) complexes
Highly efficient photosensitization of TiO_2 with diimine(diketonato)ruthenium(II) complexes, 81

Scanning Maxwell stress microscopy
Scanning Maxwell stress microscopy of photo-induced charge separation in A–S–D triad monolayers, 45
Self-assembled monolayers
Porphyrin and fullerene-based photovoltaic devices, 57
Shockwave
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Silica glass
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Soft lithography
Nanopatterning with conformable phase masks, 149
Solar cells
Highly efficient photosensitization of TiO_2 with diimine(diketonato)ruthenium(II) complexes, 81

Supramolecular chemistry
Reversible control of properties of materials by thermally irreversible photochromism, 9
Surface micro-structuring
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Surface modification
A nano-modified Si/TiO_2 composite electrode for efficient solar water splitting, 107
Surface potentials
Scanning Maxwell stress microscopy of photo-induced charge separation in A–S–D triad monolayers, 45

Thin film
A nano-modified Si/TiO_2 composite electrode for efficient solar water splitting, 107
Time-resolved shadowgraph microscopy
Micron- and submicron-sized surface patterning of silica glass by LIBWE method, 129
Titanium dioxide
Sensitization of TiO_2 with ruthenium complexes containing boronic acid functions, 91
Efficient osmium sensitizers containing 2,2′-bipyridine-4,4′-bisphosphonic acid ligand, 99
Transient absorption
Microscopic imaging of the efficiency of electron injection from excited sensitizer dye into nanocrystalline ZnO film, 69

Visible light irradiation
Dye-sensitized photocatalysts for efficient hydrogen production from aqueous I^- solution under visible light irradiation, 115

Wave-packet dynamics
Quantum dynamical simulations of ultrafast photoinduced electron-transfer processes, 19
Wet etching
Fabrication of beam homogenizers in quartz by laser micromachining, 135

Guide for Authors

Submission of Papers

Authors can upload their article as a ***LaTeX, Microsoft® (MS) Word®, WordPerfect®, PostScript or Adobe® Acrobat® PDF*** document via the Author Gateway page of this journal (http://authors.elsevier.com/journal/jphotochem), where you will also find a detailed description on its use. Alternatively, send three copies of your manuscript to one of the Editors by mail.

All authors other than those in the USA, Canada or Asia should submit their material to the **European Editor**:

Professor Monique Martin
Directeur de Recherche au CNRS, UMR ENS CNRS 8640, PASTEUR, Département de Chimie, École Normale Supérieure, 24 Rue Lohmond, 75231 Paris Cedex 05, France
FAX: +33-1-44-323325
E-MAIL: Monique.Martin@ens.fr

Authors in the USA and Canada may submit their manuscripts to the **North American Editor:**

Professor R. Schmehl
Department of Chemistry
Tulane University
New Orleans, LA 70118
USA
FAX: +1-504-865-5596
E-MAIL: russ@tulane.edu

Authors in Asia should submit their manuscripts to the **Asian Editor:**

Professor H. Masuhara
Faculty of Engineering
Department of Applied Physics
Osaka University
Yamadaoka 2-1
Suita, Osaka 565-0871
Japan
FAX: +81 6 6876 8580
E-MAIL: masuhara@ap.eng.osaka-u.ac.jp

The full postal address, fax and telephone numbers, and e-mail address of the corresponding author must be given on the first (title) page of the manuscript. Contributions are accepted on the understanding that authors have obtained the necessary authority for publication. Submission of an article is understood to imply that the article is original and unpublished and is not being considered for publication elsewhere. Upon acceptance of an article by the journal, the author(s) will be asked to transfer the copyright of the article to the publisher. This transfer will ensure the widest possible dissemination of information.

Language

Please write your text in good English.
Authors in Japan please note that information about how to have the English of your paper checked corrected and improved (*before submission*) is available from: Elsevier Japan, 4F Higashi-Azabu, 1-Chome Bldg, 1-9–15 Higashi-Azabu, Minato-ku, Tokyo 106-0044, Japan, Tel.: (+81) (3) 5561 5037; Fax: (+81) (3) 5561 5047.

Preparation of manuscripts and illustrations

Please consult the full Guide for Authors of the journal in an early issue of the year, or online at the journal's Author Gateway at http://authors.elsevier.com/journal/jphotochem

Offprints

Fifty offprints are provided free of charge to the corresponding author. Extra offprints can be ordered at prices shown on the offprint order form.

Further Information

The Author Gateway also provides detailed artwork guidelines, copyright information, frequently asked question and more. Contact details for questions arising after acceptance of an article, especially those relating to proofs, are provided after registration of an article for publication.
Visit the Author Gateway (http://authors.elsevier.com) for the facility to track accepted articles and set up e-mail alerts to inform you of when an article status has changed.


1010-6030(20040812)166:1-3;1-P